

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	38729	(substrate or wafer) near4 (expos\$5) near4 (layer or plural\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 18:31
L5	8138	(measur\$5 or detect\$3 or sens\$3) near4 (deviation or offset or error) near4 (pattern or expos\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 18:42
L6	269830	(correct\$3 or compensat\$3) near4 (error or offset or deviation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 18:43
L7	29998	(next or successive or "n+1") near4 (expos\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 18:44
L8	304	5 and 6 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 18:44
L9	12	((digital near mask) or slm or dmd or (micro near mirror)) and 8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 19:39
L10	292	8 not 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/01 19:39

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